

Atty Docket No. JCLA5662-CIP-R

Serial No. 09/817,682

**AMENDMENTS****In The Claims:**

Claim 1. (previously presented) An alignment mark configuration, which is applicable on a substrate, the alignment mark configuration comprising:

an alignment mark on the substrate, wherein the alignment mark comprises a plurality of recesses and a spacing between the neighboring recesses is "d", wherein the recess has a width of about 2 microns to about 6 microns and the spacing "d" is a range of about 6 microns to about 12 microns; and

a trench, wherein a spacing between the trench and the alignment mark is of a range between about 5d to about 80d.

Claim 2. (original) The alignment mark configuration according to claim 1, wherein the recesses include a plurality of trenches formed by a shallow trench isolation fabrication process.

Claim 3. (original) The alignment mark configuration according to claim 1, wherein the trench includes a shallow trench isolation structure.

Claim 4. (new) The alignment mark configuration according to claim 1, wherein each of the recesses is rectangular-like.

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Claim 5. (new) The alignment mark configuration according to claim 1, wherein each of the recesses is rectangular-like and is arranged in one direction side by side at long sides of the rectangular-like recesses.

Claim 6. (new) An alignment mark configuration, which is applicable on a substrate, the alignment mark configuration comprising:

an alignment mark on the substrate, wherein the alignment mark comprises a plurality of recesses, wherein each of the recesses is rectangular-like and a spacing between the neighboring recesses is "d"; and

a trench, wherein a spacing between the trench and the alignment mark is of a range between about 5d to about 80d.